



Atty. Okt. No.	308101	Client Ref. P-1810.000-US
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INFORMATION DISCLOSURE STATEMENT  
BY APPLICANT

Applicant: DUINEVELD et al.

Appl. No. 10/773,461

Filing Date: February 9, 2004

Examiner: Unknown *6/1/04* Group Art Unit: 2854 Z8S1

Date: November 2, 2004

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Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
<i>KS</i>	AR 3,573,975	04/1971	DHAKA et al.	117	212	
	BR 3,648,587	03/1972	STEVENS	95	44	
	CR 4,346,164	08/1982	TABARELLI et al.	430	311	
	OR 4,390,273	06/1983	LOEBACH et al.	355	125	
	ER 4,396,705	08/1983	AKEYAMA et al.	430	326	
	FR 4,480,910	11/1984	TAKANASHI et al.	355	30	
	GR 4,509,852	04/1985	TABARELLI et al.	355	30	
	HR 5,040,020	08/1991	RAUSCHENBACH et al.	355	53	
	IR 5,121,256	06/1992	CORLE et al.	359	664	
	JR 5,610,683	03/1997	TAKAHASHI	355	53	
	KR 5,715,039	02/1998	FUKUDA et al.	355	53	
	LR 5,825,043	10/1998	SUWA	250	548	
	MR 5,900,354	05/1999	BATCHELDER	430	395	
<i>KS</i>	NR 6,191,429	02/2001	SUWA	250	548	

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					Enclosed	No	Enclosed	No
<i>KS</i>	OR WO 99/49504	09/1999	PCT	FUKAMI et al.	X		X	
	PR EP 0023231	02/1981	EUROPE	TABARELLI et al.	X			
	QR EP 0418427	03/1991	EUROPE	MIYAKE	X		X	
	RR EP 1039511	09/2000	EUROPE	MURAKAMI et al.	X		X	
	SR DD 224448	07/1985	GERMANY	HESSE et al.		X		
	TR DD 242880	02/1987	GERMANY	KUCH		X		
	UR FR 2474708	07/1981	FRANCE	LETELLIER		X		
	VR JP 62-065326	03/1987	JAPAN	MORIUCHI	X			
	WR JP 62-121417	06/1987	JAPAN	NAKAZAWA	X			
	XR JP 63-157419	06/1988	JAPAN	NAKASUJI	X			
	YR JP 04-305915	10/1992	JAPAN	OZEKI et al.	X			
	ZR JP 04-305917	10/1992	JAPAN	OZEKI et al.	X			
<i>KS</i>	AAR JP 06-124873	05/1994	JAPAN	TAKAHASHI	X		X	

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

<i>KS</i>	BBR	M. SWITKES et al., "Immersion Lithography at 157 nm", MIT Lincoln Lab, Orlando 2001-1, December 17, 2001				
	CCR	M. SWITKES et al., "Immersion Lithography at 157 nm", J. Vac. Sci. Technol. B., Vol. 19, No. 6, November/December 2001, pp. 2353-2356.				
<i>KS</i>	DDR	M. SWITKES et al., "Immersion Lithography: Optics for the 50 nm Node", 157 Anvers-1, September 4, 2002				

Examiner *KS* Date Considered: *7-12-2005*

\*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

Atty.  
Dkt. No.

Mr.

Client Ref.

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Examiner: Unknown ~~Unknown~~ Group Art Unit: 2834 2651

U.S. PATENT DOCUMENTS

Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
<i>AR</i>	AR 6,560,032	05/2003	HATANO	359	656	
	BR 6,600,547	07/2003	WATSON et al.			
	CR 6,603,130	08/2003	BISSCHOPS et al.	250	492.1	
	DR 6,633,365	10/2003	SUENAGA	355	53	
	ER 2002/0163629	11/2002	SWITKES et al.	355	53	
	FR 2003/0123040	07/2003	ALMOGY	355	69	
	GR 2003/0174408	09/2003	ROSTALSKI et al.	359	642	
	HR 2004/0000627 A1	01/2004	SCHUSTER			
	IR 2004/0021844 A1	02/2004	SUENAGA			
	JR 2004/0075895 A1	04/2004	LIN	359	380	
<i>✓</i>	KR 2004/0109237 A1	06/2004	EPPEL et al.			

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					Enclosed	No	Enclosed	No
<i>LR</i>	LR JP 07-220990	08/1995	JAPAN	FUKUDA et al.	X			
	MR JP 10-228661	08/1998	JAPAN	KUROKAWA	X			
	NR JP 10-255319	09/1998	JAPAN	SUENAGA et al.	X			
	OR JP 10-303114	11/1998	JAPAN	SUWA	X		X	
	PR JP 10-340846	12/1998	JAPAN	KUDO	X		X	
	QR JP 2001-091849	04/2001	JAPAN	AIZAKI et al.	X			
	RR JP 07-132262	05/1995	Japan	HIRAKAWA et al.	X			
	SR JP 58-202448	11/1983	Japan	KAWAMURA et al.	X			
	TR WO 2004/019128	03/2004	PCT	OMURA et al.	X		X	
	UR WO 03/077037	09/2003	PCT	ROSTALSKI et al.	X		X	
<i>✓</i>	VR WO 03/077036	09/2003	PCT	SCHUSTER	X			

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<i>WR</i>	B.J. LIN, "Drivers, Prospects and Challenges for Immersion Lithography", TSMC, Inc., September 2002							
<i>XR</i>	B.J. LIN, "Proximity Printing Through Liquid", IBM Technical Disclosure Bulletin, Vol.20; No. 11B, April 1978, p. 4997							
<i>YR</i>	B.J. LIN, "The Paths To Subhalf-Micrometer Optical Lithography", SPIE Vol. 922, Optical/Laser Microlithography (1988), pp. 256-269							
<i>ZR</i>	G.W.W. STEVENS, "Reduction of Waste Resulting from Mask Defects", Solid State Technology, August 1978, Vol.21 008, pp. 68-72							
<i>AAR</i>	S. OWA et al., "Immersion Lithography; its potential performance and issues", SPIE Microlithography 2003, 5040-186, February 27, 2003							
<i>BBR</i>	S. OWA et al., "Advantage and Feasibility of Immersion Lithography", Proc. SPIE 5040 (2003)							

Examiner

Date Considered:

\*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

FORM PTO-1449 (modified)  
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Patent and Trademark Office

Atty. Dkt. No.	M#	Client Ref.
	308101	P-1810.000-US

**INFORMATION DISCLOSURE STATEMENT  
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Applicant: DUINEVELD et al.
Appln. No. 10/773,461
Filing Date: February 9, 2004
Examiner: Unknown <i>Unknown</i> Group Art Unit: 2854-2351

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Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
<i>JP</i>	AR 6,236,634 B1	05/2001	LEE et al.	369	112	<input checked="" type="checkbox"/>
<i>JP</i>	BR 2002/0020821 A1	02/2002	VAN SANTEN et al.	250	492	<input checked="" type="checkbox"/>

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	Document Number	Date MM/YYYY	Country	Inventor Name		Enclosed	No	Enclosed	No
<i>JP</i>	CR DD 206 607	02/1984	GERMANY	WESTPHAL et al.			X		
	DR DD 221 563	04/1985	GERMANY	PFORR et al.			X		
	ER JP 11-176727	07/1999	JAPAN	SHIRAI		X			
	FR JP 2000-058436	02/2000	JAPAN	FUJISHIMA et al.		X			
	GR WO 2004/053950 A1	06/2004	PCT	OWA		X			
	HR WO 2004/053951 A1	06/2004	PCT	MAGOME et al.		X			
	IR WO 2004/053952 A1	06/2004	PCT	MAGOME et al.		X			
	JR WO 2004/053953 A1	06/2004	PCT	NEI et al.		X			
	KR WO 2004/053954 A1	06/2004	PCT	NEI et al.		X			
	LR WO 2004/053955 A1	06/2004	PCT	HIRUKAWA et al.		X			
	MR WO 2004/053956 A1	06/2004	PCT	NAGASAKA et al.		X			
	NR WO 2004/053957 A1	06/2004	PCT	HIDAKA et al.		X			
	OR WO 2004/053958 A1	06/2004	PCT	MIZUTANI et al.		X			
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	QR WO 2004/053956 A2	06/2004	PCT	GRAUPNER		X			

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<i>JP</i>	RR	Nikon Precision Europe GmbH, "Investor Relations - Nikon's Real Solutions", May 15, 2003
	SR	H. KAWATA et al., "Optical Projection Lithography using Lenses with Numerical Apertures Greater than Unity", Microelectronic Engineering 9 (1989), pp. 31-36
	TR	J.A. HOFFNAGLE et al., "Liquid Immersion Deep-Ultraviolet Interferometric Lithography", J. Vac. Sci. Technol. B., Vol. 17, No. 6, November/December 1999, pp. 3306-3309
	UR	B.W. SMITH et al., "Immersion Optical Lithography at 193nm", FUTURE FAB International, Vol. 15, July 11, 2003
	VR	H. KAWATA et al., "Fabrication of 0.2µm Fine Patterns Using Optical Projection Lithography with an Oil Immersion Lens", Jpn. J. Appl. Phys. Vol. 31 (1992), pp. 4174-4177
	WR	G. OWEN et al., "1/8µm Optical Lithography", J. Vac. Sci. Technol. B., Vol. 10, No. 6, November/December 1992, pp. 3032-3036
	XR	H. HOGAN, "New Semiconductor Lithography Makes a Splash", PHOTONICS SPECTRA, Photonics TechnologyWorld, October 2003 Edition, pgs. 1-3
<i>JP</i>	YR	S. OWA and N. NAGASAKA, "Potential Performance and Feasibility of Immersion Lithography", NGL Workshop 2003, July 10, 2003, Slide Nos. 1-33.

Examiner <i>Kon</i> <i>Buts</i>	Date Considered: <i>7-12-2005</i>
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Date: November 2, 2004 Page 4 of 4

Examiner's Initials	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
14	ZR	2004/0119954	06/2004 KAWASHIMA et al.	355	30	
12	AAR	2004/0125351	07/2004 KRAUTSCHIK et al.	355	53	
	BBR					
	CCR					
	DDR					
	EER					
	FFR					
	GGR					

FOREIGN PATENT DOCUMENTS						English Abstract		Translation Readily Available	
	Document Number	Date MM/YYYY	Country	Inventor Name		Enclosed	No	Enclosed	No
12	HHR	WO 2004/055803 A1	07/2004	PCT	VAN SANTEN	X		X	
14	IIR	WO 2004/057589 A1	07/2004	PCT	NEIJZEN et al.	X		X	
12	JJR	WO 2004/057590 A1	07/2004	PCT	VAN SANTEN et al.	X		X	
14	KKR	JP 2004-193252	07/2004	Japan	Not Available	X			
	LLR								
	MMF								
	NNR								
	OOR								

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	QQR	H. HATA, "The Development of Immersion Exposure Tools", Litho Forum, International SEMATECH, Los Angeles, January 27-29, 2004, Slide Nos. 1-22			
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	SSR	"Depth-of-Focus Enhancement Using High Refractive Index Layer on the Imaging Layer", IBM Technical Disclosure Bulletin, Vol. 27, No. 11, April 1985, p. 6521			
	TTR	A. SUZUKI, "Lithography Advances on Multiple Fronts", EEdesign, EE Times, January 5, 2004			
✓	UUR	B. LIN, "The $k_3$ coefficient in nonparaxial $\lambda/NA$ scaling equations for resolution, depth of focus, and immersion lithography, <i>J. Microlith., Microfab., Microsyst.</i> 1(1):7-12 (2002)			
	VVR				
	WWI				
	XXR				
	YYR				
	ZZR				

Examiner: <i>Lee H. Hata</i>	Date Considered: 7/2/2005
*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.	